

Abstract

A metal diaphragm valve for use *inter alia* in semiconductor facilities. This metal diaphragm valve is so designed as to reduce the fluid resistance of the fluid path from the valve chamber to the outflow path of the body and allows a large quantity of fluid to flow in spite of its small size.

The metal diaphragm valve of the present invention comprises a body 2 provided with an inflow path 6, a valve chamber 8 and an outflow path 7 and a metal diaphragm 3, driving means 4 and a ring-shaped groove 5, wherein the diameter D of the inflow path 6 is larger than the width W of the ring-shaped groove 5 and the effective cross-sectional area of the regions where the ring-shaped groove 5 and the outflow path 7 intersect one another is larger than the transverse cross-sectional area of the outflow path 7.



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